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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)																
Lt	E			M. E. Williams et al., Magnetic Levitation Scanning Stages for Extreme Ultraviolet Lithography, ASPE 14th annual meeting, Monterey CA., November 1999												
St	F			John B. Wronosky, et al., Waser and Reticle Positioning System for the Extreme Ultraviolet Lithography Engineering Test Stand, SPIE, February 2000												
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